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PATENT
30205/37456

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application of: Geun Su Lee et al.) Group Art Unit: 1752
Serial No.: 09/884,313) Examiner: Yvette C. Thornton
Filed: June 19, 2001) For: Photoresist Polymer for Top-
Surface Imaging Process by
Silylation and Photoresist
Composition Containing the Same

#13

ASSOCIATE POWER OF ATTORNEY

Commissioner for Patents
P.O. Box 1450
Alexandria, Virginia 22313-1450

Sir:

The undersigned attorney of record in the above-identified application hereby appoints as associate attorney:

Michael R. Hull (Reg. No. 35,902)

to prosecute this application, to make alterations or amendments therein, and to transact any and all business in the Patent and Trademark Office connected therewith.

Hereafter, please address all communications to:

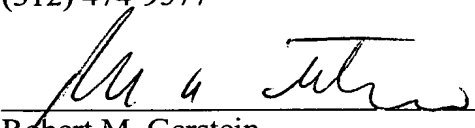
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Respectfully submitted,

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August 7, 2003

By:


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